

8<sup>th</sup> Biennial International  
Conference on Organic Synthesis

**Balticum Organicum Syntheticum**

July 6-9, 2014, Vilnius

**Program and Abstract Book**

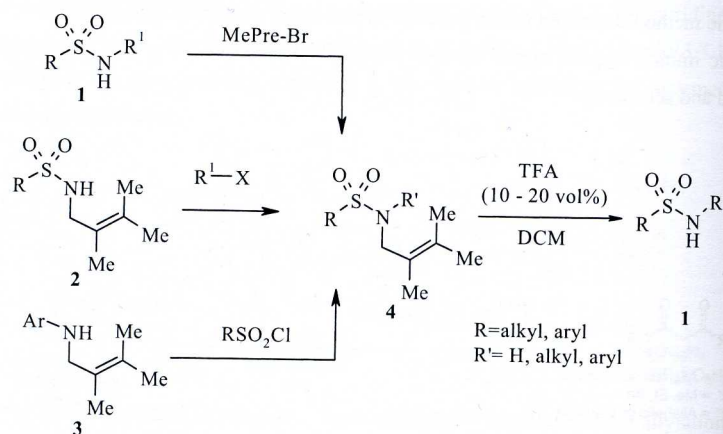
## ACID-LABILE METHYLPRENYL PROTECTION FOR SULFONAMIDES

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Sulfonamide group may often require protection during the synthesis of complex compounds due to relative acidity and nucleophilicity in deprotonated form. The few known protecting groups for sulfonamides (*t*-Bu, Bn, DPM, DMB or MP) suffer from the limited ways of installation and side-product formation during deprotection step. In our poster, we report acid-labile methylprenyl group as sulfonamide protection.

The installation of methylprenyl group can be realized through *N*-alkylation of sulfonamides with methylprenyl bromide, *N*-alkylation or arylation of *N*-methylprenyl sulfonamides 2, or sulfonylation of methylprenyl anilines 3<sup>1</sup>.



Cleavage of methylprenyl group in protected sulfonamides 4 proceeds efficiently in the presence of TFA solution in DCM. In most cases the additional purification was not required and the yield of sulfonamide 1 was excellent. Methylprenyl group is stable to catalytic hydrogenation conditions at 1 atm H<sub>2</sub> pressure, as well as in presence of base, DDQ, NIS and LAH.

## References:

1. Lober O.; Kawatsura M.; Hartwig J. F. *J. Am. Chem. Soc.* **2001**, 123, 4366.